

PATENT ABSTRACTS OF JAPAN

(11) Publication number : 2001-332523

(43) Date of publication of application : 30. 11. 2001

(51) Int. Cl.

H01L 21/304

B08B 3/12

H01L 21/306

(21) Application number : 2000-147894

(71) Applicant : DAINIPPON SCREEN MFG CO LTD

(22) Date of filing : 19. 05. 2000

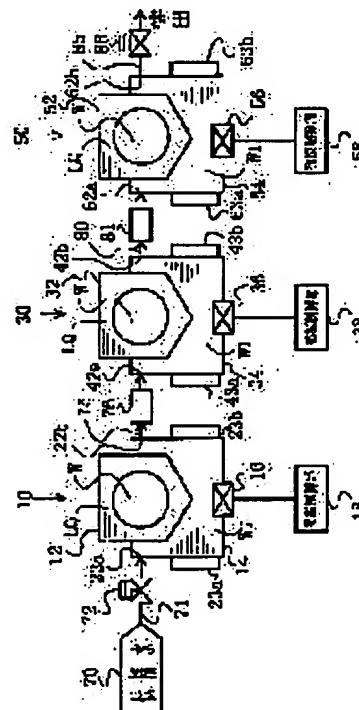
(72) Inventor : SHIBAYAMA NORIYUKI
MURAOKA YUSUKE

(54) SUBSTRATE TREATING DEVICE

(57) Abstract:

PROBLEM TO BE SOLVED: To suppress a drop in the yield of a device by suppressing the occurrence of bubbles in running water and improving the treatment efficiency of the cleaning, etc., of a substrate.

SOLUTION: This substrate treating device is provided with a treating tank 10 in which treatment, such as cleaning, etc., is performed on a wafer W while the wafer W is dipped in a treating liquid LQ; an outer tank 14 which is arranged beside and under the tank 10, has a hermetically sealed structure, and contains the running water WT, and an ultrasonic vibrating body 16 which gives an ultrasonic wave to the treating liquid LQ contained in the tank 10 through the running water WT contained in the outer tank 14.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]